

=> d his

(FILE 'HOME' ENTERED AT 17:59:41 ON 20 MAY 2003)

FILE 'REGISTRY' ENTERED AT 17:59:56 ON 20 MAY 2003

L1 SCREEN 964 AND 970 AND 1015 AND 1051  
L2 STRUCTURE UPLOADED  
L3 QUE L2 AND L1  
L4 0 S L3 SSS SAM

FILE 'CAPLUS, HCAPLUS, USPATFULL, USPAT2' ENTERED AT 18:00:24 ON 20 MAY 2003

L5 0 S L4

FILE 'REGISTRY' ENTERED AT 18:00:51 ON 20 MAY 2003

L6 SCREEN 964 AND 970 AND 1015 AND 1051 AND 2067  
L7 STRUCTURE UPLOADED  
L8 QUE L7 AND L6  
L9 0 S L8 SSS SAM

FILE 'CAPLUS, HCAPLUS, USPATFULL, USPAT2' ENTERED AT 18:01:15 ON 20 MAY 2003

L10 0 S L9

FILE 'REGISTRY' ENTERED AT 18:01:25 ON 20 MAY 2003

L11 0 S 1-HYDROXY-3-1-ACRYLOYLOXY-12-DIMETHYLPROPYLADAMANTINE  
L12 0 S 1-HYDROXY-3-1-ACRYLOYLOXY-12-DIMETHYLPROPYL ADAMANTINE  
L13 0 S 1-HYDROXY-3-1-ACRYLOYLOXY-12-DIMETHYLPROPYL ADAMANTANE  
L14 0 S 1-HYDROXY-3-1-ACRYLOYLOXY-12-DIMETHYLPROPYLADAMANTANE

FILE 'HOME' ENTERED AT 18:03:18 ON 20 MAY 2003

FILE 'REGISTRY' ENTERED AT 18:07:37 ON 20 MAY 2003

L15 SCREEN 970 AND 2067  
L16 STRUCTURE UPLOADED  
L17 QUE L16 AND L15  
L18 5 S L17 SSS SAM

FILE 'CAPLUS, HCAPLUS, USPATFULL, USPAT2' ENTERED AT 18:08:32 ON 20 MAY 2003

L19 17 S L18  
L20 8 DUPLICATE REMOVE L19 (9 DUPLICATES REMOVED)

FILE 'HOME' ENTERED AT 18:09:19 ON 20 MAY 2003

FILE 'REGISTRY' ENTERED AT 18:10:06 ON 20 MAY 2003

L21 SCREEN 970 AND 2076 AND 2067  
L22 STRUCTURE UPLOADED  
L23 QUE L22 AND L21  
L24 0 S L23

FILE 'CAPLUS, HCAPLUS, USPATFULL, USPAT2' ENTERED AT 18:10:45 ON 20 MAY 2003

L25 0 S L24

FILE 'HOME' ENTERED AT 18:10:54 ON 20 MAY 2003

FILE 'REGISTRY' ENTERED AT 18:13:10 ON 20 MAY 2003

L26 SCREEN 970 AND 2067  
L27 STRUCTURE UPLOADED  
L28 QUE L27 AND L26  
L29 0 S L28 SSS SAM

STN-CAS  
SEARCH  
DO NOT REMOVE

FILE 'CAPLUS, HCAPLUS, USPATFULL, USPAT2' ENTERED AT 18:13:35 ON 20 MAY  
2003

L30

0 S L29

=> ....Testing the current file.... screen

ENTER SCREEN EXPRESSION OR (END):end

=> screen 970 AND 2067

L15 SCREEN CREATED

=>

Uploading C:\Program Files\Stnexp\Queries\09463059.str

L16 STRUCTURE UPLOADED

=> que L16 AND L15

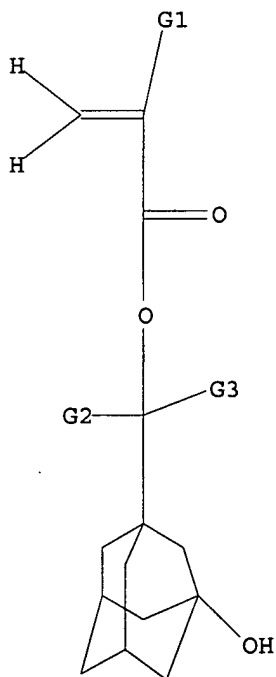
L17 QUE L16 AND L15

=> d

L17 HAS NO ANSWERS

L15 SCR 970 AND 2067

L16 STR



G1 Me,H

G2 H,Ak,Cy

G3 Cy,Ak

Structure attributes must be viewed using STN Express query preparation.

L17 QUE ABB=ON PLU=ON L16 AND L15

=> s l17 sss sam

SAMPLE SEARCH INITIATED 18:08:17 FILE 'REGISTRY'

SAMPLE SCREEN SEARCH COMPLETED - 7 TO ITERATE

100.0% PROCESSED 7 ITERATIONS

5 ANSWERS

SEARCH TIME: 00.00.01

FULL FILE PROJECTIONS: ONLINE \*\*COMPLETE\*\*  
BATCH \*\*COMPLETE\*\*  
PROJECTED ITERATIONS: 7 TO 298  
PROJECTED ANSWERS: 5 TO 234

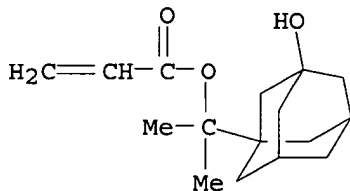
L18 5 SEA SSS SAM L16 AND L15

=> d

L18 ANSWER 1 OF 5 REGISTRY COPYRIGHT 2003 ACS  
RN 450410-08-9 REGISTRY  
CN 2-Propenoic acid, 3,5-dihydroxytricyclo[3.3.1.1<sup>3,7</sup>]dec-1-yl ester, polymer  
with 1-(3-hydroxytricyclo[3.3.1.1<sup>3,7</sup>]dec-1-yl)-1-methylethyl 2-propenoate  
(9CI) (CA INDEX NAME)  
MF (C16 H24 O3 . C13 H18 O4)x  
CI PMS  
PCT Polyacrylic  
SR CA  
LC STN Files: CA, CAPLUS, USPATFULL

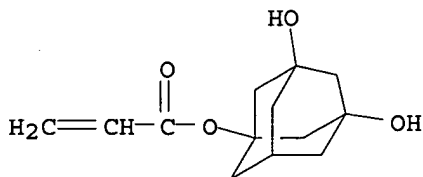
CM 1

CRN 262608-27-5  
CMF C16 H24 O3



CM 2

CRN 216581-85-0  
CMF C13 H18 O4



1 REFERENCES IN FILE CA (1957 TO DATE)  
1 REFERENCES IN FILE CAPLUS (1957 TO DATE)

=> FIL CAPLUS HCAPLUS USPATFULL USPAT2  
COST IN U.S. DOLLARS  
FULL ESTIMATED COST

SINCE FILE	TOTAL
ENTRY	SESSION
2.48	143.18

FILE 'CAPLUS' ENTERED AT 18:08:32 ON 20 MAY 2003  
USE IS SUBJECT TO THE TERMS OF YOUR STN CUSTOMER AGREEMENT.

PLEASE SEE "HELP USAGETERMS" FOR DETAILS.  
COPYRIGHT (C) 2003 AMERICAN CHEMICAL SOCIETY (ACS)

FILE 'HCAPLUS' ENTERED AT 18:08:32 ON 20 MAY 2003  
USE IS SUBJECT TO THE TERMS OF YOUR STN CUSTOMER AGREEMENT.  
PLEASE SEE "HELP USAGETERMS" FOR DETAILS.  
COPYRIGHT (C) 2003 AMERICAN CHEMICAL SOCIETY (ACS)

FILE 'USPATFULL' ENTERED AT 18:08:32 ON 20 MAY 2003  
CA INDEXING COPYRIGHT (C) 2003 AMERICAN CHEMICAL SOCIETY (ACS)

FILE 'USPAT2' ENTERED AT 18:08:32 ON 20 MAY 2003  
CA INDEXING COPYRIGHT (C) 2003 AMERICAN CHEMICAL SOCIETY (ACS)

=> d his

(FILE 'HOME' ENTERED AT 17:59:41 ON 20 MAY 2003)

FILE 'REGISTRY' ENTERED AT 17:59:56 ON 20 MAY 2003

L1 SCREEN 964 AND 970 AND 1015 AND 1051  
L2 STRUCTURE UPLOADED  
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FILE 'CAPLUS, HCAPLUS, USPATFULL, USPAT2' ENTERED AT 18:00:24 ON 20 MAY 2003

L5 0 S L4

FILE 'REGISTRY' ENTERED AT 18:00:51 ON 20 MAY 2003

L6 SCREEN 964 AND 970 AND 1015 AND 1051 AND 2067  
L7 STRUCTURE UPLOADED  
L8 QUE L7 AND L6  
L9 0 S L8 SSS SAM

FILE 'CAPLUS, HCAPLUS, USPATFULL, USPAT2' ENTERED AT 18:01:15 ON 20 MAY 2003

L10 0 S L9

FILE 'REGISTRY' ENTERED AT 18:01:25 ON 20 MAY 2003

L11 0 S 1-HYDROXY-3-1-ACRYLOYLOXY-12-DIMETHYLPROPYLADAMANTINE  
L12 0 S 1-HYDROXY-3-1-ACRYLOYLOXY-12-DIMETHYLPROPYL ADAMANTINE  
L13 0 S 1-HYDROXY-3-1-ACRYLOYLOXY-12-DIMETHYLPROPYL ADAMANTANE  
L14 0 S 1-HYDROXY-3-1-ACRYLOYLOXY-12-DIMETHYLPROPYLADAMANTANE

FILE 'HOME' ENTERED AT 18:03:18 ON 20 MAY 2003

FILE 'REGISTRY' ENTERED AT 18:07:37 ON 20 MAY 2003

L15 SCREEN 970 AND 2067  
L16 STRUCTURE UPLOADED  
L17 QUE L16 AND L15  
L18 5 S L17 SSS SAM

FILE 'CAPLUS, HCAPLUS, USPATFULL, USPAT2' ENTERED AT 18:08:32 ON 20 MAY 2003

=> s l18

L19 17 L18

=> duplicates remove

ENTER L# LIST OR (END):l19

DUPLICATE PREFERENCE IS 'CAPLUS, HCAPLUS, USPATFULL'

KEEP DUPLICATES FROM MORE THAN ONE FILE? Y/(N):n

PROCESSING COMPLETED FOR L19

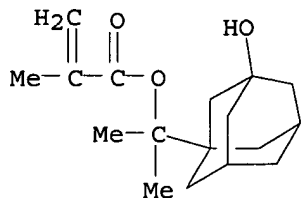
L20 8 DUPLICATE REMOVE L19 (9 DUPLICATES REMOVED)

=> d 120 1-8 ibib hitstr

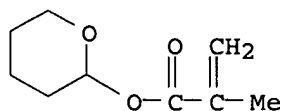
L20 ANSWER 1 OF 8 CAPLUS COPYRIGHT 2003 ACS DUPLICATE 1  
ACCESSION NUMBER: 2002:654986 CAPLUS  
DOCUMENT NUMBER: 137:192769  
TITLE: Polymeric compound and resin composition for photoresist  
INVENTOR(S): Ushirogouchi, Toru; Okino, Takeshi; Asakawa, Koji; Shida, Naomi; Funaki, Yoshinori; Tsutsumi, Kiyoharu; Takaragi, Akira; Inoue, Keizo  
PATENT ASSIGNEE(S): Kabushiki Kaisha Toshiba, Japan; Daicel Chemical Industries, Ltd.  
SOURCE: U.S., 24 pp.  
CODEN: USXXAM  
DOCUMENT TYPE: Patent  
LANGUAGE: English  
FAMILY ACC. NUM. COUNT: 1  
PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
US 6440636	B1	20020827	US 2000-703677	20001102
PRIORITY APPLN. INFO.:			US 2000-703677	20001102

IT 338790-67-3P 450410-08-9P  
RL: PRP (Properties); SPN (Synthetic preparation); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses)  
(polymeric compd. and resin compn. for photoresist)  
RN 338790-67-3 CAPLUS  
CN 2-Propenoic acid, 2-methyl-, 1-(3-hydroxytricyclo[3.3.1.1<sup>3,7</sup>]dec-1-yl)-1-methylethyl ester, polymer with tetrahydro-2H-pyran-2-yl 2-methyl-2-propenoate (9CI) (CA INDEX NAME)  
CM 1  
CRN 324761-49-1  
CMF C17 H26 O3



CM 2  
CRN 52858-59-0  
CMF C9 H14 O3



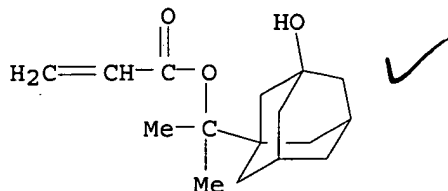
RN 450410-08-9 CAPLUS  
CN 2-Propenoic acid, 3,5-dihydroxytricyclo[3.3.1.1.3,7]dec-1-yl ester, polymer with 1-(3-hydroxytricyclo[3.3.1.1.3,7]dec-1-yl)-1-methylethyl 2-propenoate

(9CI) (CA INDEX NAME)

CM 1

CRN 262608-27-5

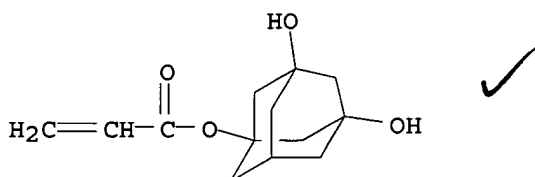
CMF C16 H24 O3



CM 2

CRN 216581-85-0

CMF C13 H18 O4



REFERENCE COUNT: 13 THERE ARE 13 CITED REFERENCES AVAILABLE FOR THIS RECORD. ALL CITATIONS AVAILABLE IN THE RE FORMAT

L20 ANSWER 2 OF 8 CAPLUS COPYRIGHT 2003 ACS DUPLICATE 2  
ACCESSION NUMBER: 2002:292089 CAPLUS  
DOCUMENT NUMBER: 136:316934  
TITLE: Positive-working photoresist composition for  
fabrication of semiconductor device  
INVENTOR(S): Sato, Kenichiro  
PATENT ASSIGNEE(S): Fuji Photo Film Co., Ltd., Japan  
SOURCE: Jpn. Kokai Tokkyo Koho, 51 pp.  
CODEN: JKXXAF  
DOCUMENT TYPE: Patent  
LANGUAGE: Japanese  
FAMILY ACC. NUM. COUNT: 1  
PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
JP 2002116544	A2	20020419	JP 2000-310761	20001011
PRIORITY APPLN. INFO.:			JP 2000-310761	20001011
OTHER SOURCE(S):	MARPAT 136:316934			
IT	412015-88-4			

RL: TEM (Technical or engineered material use); USES (Uses)  
(pos.-working photoresist compn. for fabrication of semiconductor device)

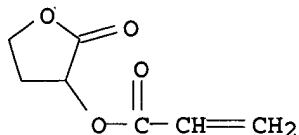
RN 412015-88-4 CAPLUS

CN 2-Propenoic acid, 1-(3-hydroxytricyclo[3.3.1.1.3,7]dec-1-yl)-1-methylethyl ester, polymer with 2,5-furandione, 1,2,3,4,4a,5,8,8a-octahydro-1,4:5,8-dimethanonaphthalene and tetrahydro-2-oxo-3-furanyl 2-propenoate (9CI)  
(CA INDEX NAME)

CM 1

CRN 328249-37-2

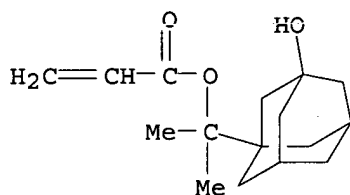
CMF C7 H8 O4



CM 2

CRN 262608-27-5

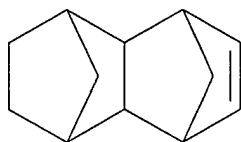
CMF C16 H24 O3



CM 3

CRN 21635-90-5

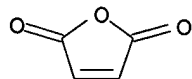
CMF C12 H16



CM 4

CRN 108-31-6

CMF C4 H2 O3



L20 ANSWER 3 OF 8 CAPLUS COPYRIGHT 2003 ACS

DUPLICATE 3

ACCESSION NUMBER: 2001:347119 CAPLUS

DOCUMENT NUMBER: 134:346475

TITLE: Adamantyl-containing polymer for photoresist and polymer composition for photoresist

INVENTOR(S): Gokochi, Toru; Okino, Takeshi; Asakawa, Koji; Shinoda, Naomi; Funaki, Katsunori; Tsutsumi, Kiyoharu; Horai,



PATENT ASSIGNEE(S): Akira; Inoue, Keizo  
SOURCE: Toshiba Corp., Japan; Daicel Chemical Industries, Ltd.  
Jpn. Kokai Tokkyo Koho, 23 pp.  
CODEN: JKXXAF  
DOCUMENT TYPE: Patent  
LANGUAGE: Japanese  
FAMILY ACC. NUM. COUNT: 1  
PATENT INFORMATION:

5/15/01  
11-2-99

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
JP 2001131232	A2	20010515	JP 1999-312329	19991102
PRIORITY APPLN. INFO.: IT 338790-67-3P			JP 1999-312329	19991102

RL: IMF (Industrial manufacture); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses)  
(adamantyl-contg. polymer for etching-resistant photoresist for semiconductor device fabrication)

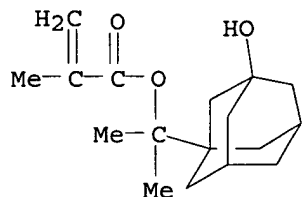
RN 338790-67-3 CAPLUS

CN 2-Propenoic acid, 2-methyl-, 1-(3-hydroxytricyclo[3.3.1.1<sup>3,7</sup>]dec-1-yl)-1-methylethyl ester, polymer with tetrahydro-2H-pyran-2-yl  
2-methyl-2-propenoate (9CI) (CA INDEX NAME)

CM 1

CRN 324761-49-1

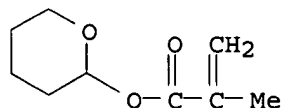
CMF C17 H26 O3



CM 2

CRN 52858-59-0

CMF C9 H14 O3



L20 ANSWER 4 OF 8 CAPLUS COPYRIGHT 2003 ACS DUPLICATE 4  
ACCESSION NUMBER: 2001:117245 CAPLUS  
DOCUMENT NUMBER: 134:170832  
TITLE: Positive-working photoresist composition suitable for exposed with ArF excimer laser  
INVENTOR(S): Sato, Kenichiro; Shirakawa, Hiroshi; Aogo, Toshiaki  
PATENT ASSIGNEE(S): Fuji Photo Film Co., Ltd., Japan  
SOURCE: Jpn. Kokai Tokkyo Koho, 48 pp.  
CODEN: JKXXAF  
DOCUMENT TYPE: Patent  
LANGUAGE: Japanese  
FAMILY ACC. NUM. COUNT: 1

PATENT INFORMATION:

2/16/01

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
JP 2001042535	A2	20010216	JP 1999-211370	19990726
PRIORITY APPLN. INFO.:			JP 1999-211370	19990726

IT 324761-53-7P 324761-58-2P

RL: SPN (Synthetic preparation); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses)  
(alicyclic polymer in pos.-working photoresist compn.)

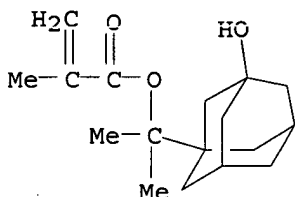
RN 324761-53-7 CAPLUS

CN 2-Propenoic acid, 2-methyl-, 1-(3-hydroxytricyclo[3.3.1.1<sup>3,7</sup>]dec-1-yl)-1-methylethyl ester, polymer with tetrahydro-2-methyl-5-oxo-3-furanyl 2-methyl-2-propenoate (9CI) (CA INDEX NAME)

CM 1

CRN 324761-49-1

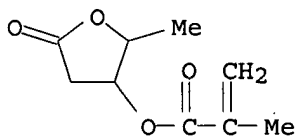
CMF C17 H26 O3



CM 2

CRN 324761-23-1

CMF C9 H12 O4



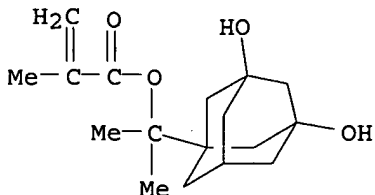
RN 324761-58-2 CAPLUS

CN 2-Propenoic acid, 2-methyl-, 1-(3,5-dihydroxytricyclo[3.3.1.1<sup>3,7</sup>]dec-1-yl)-1-methylethyl ester, polymer with tetrahydro-4,4-dimethyl-2-oxo-3-furanyl 2-methyl-2-propenoate (9CI) (CA INDEX NAME)

CM 1

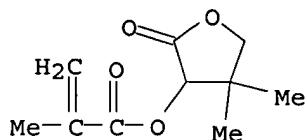
CRN 324761-57-1

CMF C17 H26 O4



CM 2

CRN 156938-13-5  
CMF C10 H14 O4



L20 ANSWER 5 OF 8 CAPLUS COPYRIGHT 2003 ACS DUPLICATE 5  
ACCESSION NUMBER: 2001:117244 CAPLUS  
DOCUMENT NUMBER: 134:170858  
TITLE: Positive-working photoresist composition suitable for  
exposed with ArF excimer laser  
INVENTOR(S): Sato, Kenichiro; Shirakawa, Hiroshi; Aogo, Toshiaki  
PATENT ASSIGNEE(S): Fuji Photo Film Co., Ltd., Japan  
SOURCE: Jpn. Kokai Tokkyo Koho, 48 pp.  
CODEN: JKXXAF  
DOCUMENT TYPE: Patent  
LANGUAGE: Japanese  
FAMILY ACC. NUM. COUNT: 1  
PATENT INFORMATION:

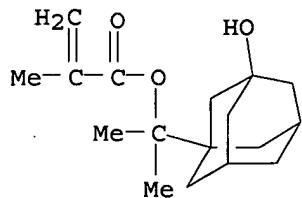
2/16/01

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
JP 2001042534	A2	20010216	JP 1999-211369	19990726
PRIORITY APPLN. INFO.:			JP 1999-211369	19990726

IT 324761-53-7P 324761-58-2P  
RL: SPN (Synthetic preparation); TEM (Technical or engineered material  
use); PREP (Preparation); USES (Uses)  
(alicyclic polymer in pos.-working photoresist compn.)  
RN 324761-53-7 CAPLUS  
CN 2-Propenoic acid, 2-methyl-, 1-(3-hydroxytricyclo[3.3.1.1<sup>3,7</sup>]dec-1-yl)-1-  
methylethyl ester, polymer with tetrahydro-2-methyl-5-oxo-3-furanyl  
2-methyl-2-propenoate (9CI) (CA INDEX NAME)

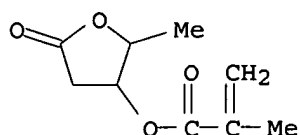
CM 1

CRN 324761-49-1  
CMF C17 H26 O3



CM 2

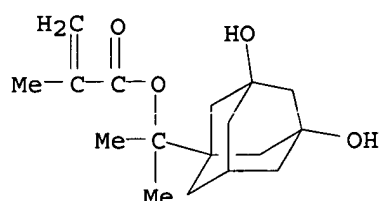
CRN 324761-23-1  
CMF C9 H12 O4



RN 324761-58-2 CAPLUS  
 CN 2-Propenoic acid, 2-methyl-, 1-(3,5-dihydroxytricyclo[3.3.1.1.3,7]dec-1-yl)-1-methylethyl ester, polymer with tetrahydro-4,4-dimethyl-2-oxo-3-furanyl 2-methyl-2-propenoate (9CI) (CA INDEX NAME)

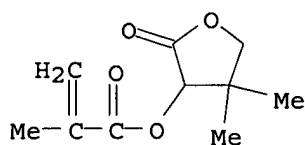
CM 1

CRN 324761-57-1  
 CMF C17 H26 O4



CM 2

CRN 156938-13-5  
 CMF C10 H14 O4



L20 ANSWER 6 OF 8 CAPLUS COPYRIGHT 2003 ACS DUPLICATE 6  
 ACCESSION NUMBER: 2001:117243 CAPLUS  
 DOCUMENT NUMBER: 134:170831  
 TITLE: Positive-working photoresist composition suitable for exposed with ArF excimer laser  
 INVENTOR(S): Sato, Kenichiro; Shirakawa, Hiroshi; Aogo, Toshiaki  
 PATENT ASSIGNEE(S): Fuji Photo Film Co., Ltd., Japan  
 SOURCE: Jpn. Kokai Tokkyo Koho, 47 pp.  
 CODEN: JKXXAF  
 DOCUMENT TYPE: Patent  
 LANGUAGE: Japanese  
 FAMILY ACC. NUM. COUNT: 1  
 PATENT INFORMATION:

2/16/01

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
JP 2001042533	A2	20010216	JP 1999-211368	19990726
PRIORITY APPLN. INFO.:			JP 1999-211368	19990726

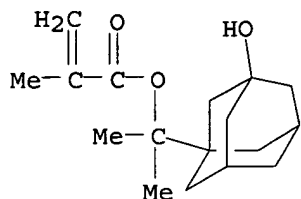
IT 324761-53-7P.324761-58-2P

RL: SPN (Synthetic preparation); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses)  
 (alicyclic polymer in pos.-working photoresist compn.)

RN 324761-53-7 CAPLUS  
 CN 2-Propenoic acid, 2-methyl-, 1-(3-hydroxytricyclo[3.3.1.1<sup>3,7</sup>]dec-1-yl)-1-methylethyl ester, polymer with tetrahydro-2-methyl-5-oxo-3-furanyl  
 2-methyl-2-propenoate (9CI) (CA INDEX NAME)

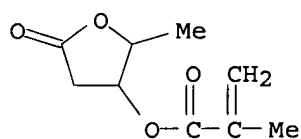
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CM 2

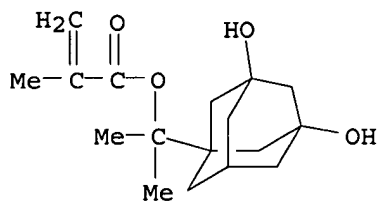
CRN 324761-23-1  
 CMF C9 H12 O4



RN 324761-58-2 CAPLUS  
 CN 2-Propenoic acid, 2-methyl-, 1-(3,5-dihydroxytricyclo[3.3.1.1<sup>3,7</sup>]dec-1-yl)-1-methylethyl ester, polymer with tetrahydro-4,4-dimethyl-2-oxo-3-furanyl  
 2-methyl-2-propenoate (9CI) (CA INDEX NAME)

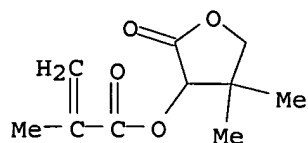
CM 1

CRN 324761-57-1  
 CMF C17 H26 O4



CM 2

CRN 156938-13-5  
 CMF C10 H14 O4



L20 ANSWER 7 OF 8 CAPLUS COPYRIGHT 2003 ACS DUPLICATE 7  
 ACCESSION NUMBER: 2001:117242 CAPLUS  
 DOCUMENT NUMBER: 134:170830  
 TITLE: Positive-working photoresist composition suitable for exposed with ArF excimer laser  
 INVENTOR(S): Sato, Kenichiro; Shirakawa, Hiroshi; Aogo, Toshiaki  
 PATENT ASSIGNEE(S): Fuji Photo Film Co., Ltd., Japan  
 SOURCE: Jpn. Kokai Tokkyo Koho, 47 pp.  
 CODEN: JKXXAF  
 DOCUMENT TYPE: Patent  
 LANGUAGE: Japanese  
 FAMILY ACC. NUM. COUNT: 1  
 PATENT INFORMATION:

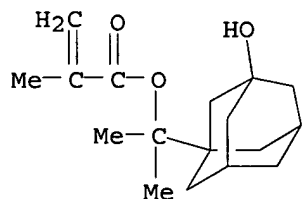
PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
JP 2001042532	A2	20010216	JP 1999-211367	19990726
PRIORITY APPLN. INFO.:			JP 1999-211367	19990726

IT 324761-53-7P 324761-58-2P  
 RL: SPN (Synthetic preparation); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses)  
 (alicyclic polymer in pos.-working photoresist compn.)  
 RN 324761-53-7 CAPLUS  
 CN 2-Propenoic acid, 2-methyl-, 1-(3-hydroxytricyclo[3.3.1.1<sup>3,7</sup>]dec-1-yl)-1-methylethyl ester, polymer with tetrahydro-2-methyl-5-oxo-3-furanyl 2-methyl-2-propenoate (9CI) (CA INDEX NAME)

CM 1

CRN 324761-49-1

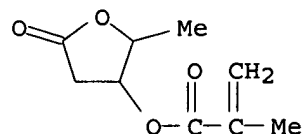
CMF C17 H26 O3



CM 2

CRN 324761-23-1

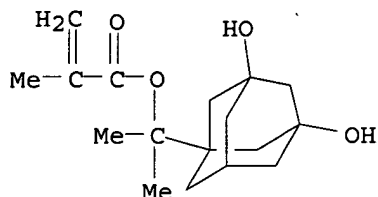
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RN 324761-58-2 CAPLUS  
CN 2-Propenoic acid, 2-methyl-, 1-(3,5-dihydroxytricyclo[3.3.1.1<sup>3,7</sup>]dec-1-yl)-  
1-methylethyl ester, polymer with tetrahydro-4,4-dimethyl-2-oxo-3-furanyl  
2-methyl-2-propenoate (9CI) (CA INDEX NAME)

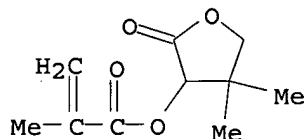
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CRN 324761-57-1  
CMF C17 H26 O4



CM 2

CRN 156938-13-5  
CMF C10 H14 O4



L20 ANSWER 8 OF 8 CAPLUS COPYRIGHT 2003 ACS DUPLICATE 8  
ACCESSION NUMBER: 2001:98658 CAPLUS  
DOCUMENT NUMBER: 134:170817  
TITLE: Positive-working photoresist composition for exposure  
to far ultraviolet light  
INVENTOR(S): Sato, Kenichiro; Kodama, Kunihiro; Aogo, Toshiaki  
PATENT ASSIGNEE(S): Fuji Photo Film Co., Ltd., Japan  
SOURCE: Jpn. Kokai Tokkyo Koho, 47 pp.  
CODEN: JKXXAF  
DOCUMENT TYPE: Patent  
LANGUAGE: Japanese  
FAMILY ACC. NUM. COUNT: 1  
PATENT INFORMATION:

2/9/01

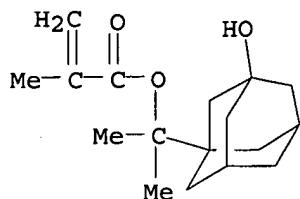
PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
JP 2001033969	A2	20010209	JP 1999-203676	19990716
PRIORITY APPLN. INFO.:			JP 1999-203676	19990716

IT 324761-53-7P 324761-58-2P  
RL: IMF (Industrial manufacture); TEM (Technical or engineered material  
use); PREP (Preparation); USES (Uses)  
(pos.-working photoresist compn. contg. polymer with alicyclic group  
for exposure to far UV light)

RN 324761-53-7 CAPLUS  
CN 2-Propenoic acid, 2-methyl-, 1-(3-hydroxytricyclo[3.3.1.1<sup>3,7</sup>]dec-1-yl)-1-  
methylethyl ester, polymer with tetrahydro-2-methyl-5-oxo-3-furanyl  
2-methyl-2-propenoate (9CI) (CA INDEX NAME)

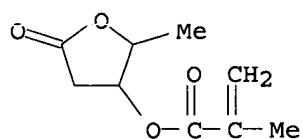
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CRN 324761-49-1  
CMF C17 H26 O3



CM 2

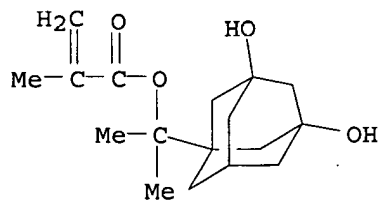
CRN 324761-23-1  
CMF C9 H12 O4



RN 324761-58-2 CAPLUS  
CN 2-Propenoic acid, 2-methyl-, 1-(3,5-dihydroxytricyclo[3.3.1.1.3,7]dec-1-yl)-1-methylethyl ester, polymer with tetrahydro-4,4-dimethyl-2-oxo-3-furanyl 2-methyl-2-propenoate (9CI) (CA INDEX NAME)

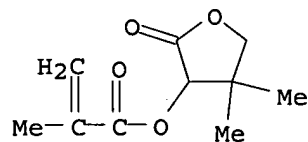
CM 1

CRN 324761-57-1  
CMF C17 H26 O4



CM 2

CRN 156938-13-5  
CMF C10 H14 O4







## Patent Assignment Abstract of Title

### Total Assignments: 2

**Application #:** 09703677 **Filing Dt:** 11/02/2000 **Patent #:** 6440636 **Issue Dt:** 08/27/2002

**PCT #:** NONE

**Publication #:** NONE **Pub Dt:**

**Inventors:** Toru Ushirogouchi, Takeshi Okino, Koji Asakawa, Naomi Shida, Yoshinori Funaki, Kiyoharu Tsutsumi, Akira Takaragi, Keizo Inoue

**Title:** POLYMERIC COMPOUND AND RESIN COMPOSITION FOR PHOTORESIST

### Assignment: 1

**Reel/Frame:** 011434/0499 **Received:** 01/22/2001 **Recorded:** 11/02/2000 **Mailed:** 03/29/2001 **Pages:** 3

**Conveyance:** ASSIGNMENT OF ASSIGNORS INTEREST (SEE DOCUMENT FOR DETAILS).

**Assignors:** USHIROGOUCHI, TORU

**Exec Dt:** 10/23/2000

OKINO, TAKESHI

**Exec Dt:** 10/23/2000

ASAKAWA, KOJI

**Exec Dt:** 10/23/2000

SHIDA, NAOMI

**Exec Dt:** 10/23/2000

**Assignee:** KABUSHIKI KAISHA TOSHIBA

72 HORIKAWA-CHO, SAIWAI-KU

KAWASAKI-SHI KANAGAWA-KEN, JAPAN

**Correspondent:** BIRCH, STEWART, KOLASCH & BIRCH, LLP

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### Assignment: 2

**Reel/Frame:** 011434/0506 **Received:** 01/22/2001 **Recorded:** 11/02/2000 **Mailed:** 03/29/2001 **Pages:** 3

**Conveyance:** ASSIGNMENT OF ASSIGNORS INTEREST (SEE DOCUMENT FOR DETAILS).

**Assignors:** FUNAKI, YOSHINORI

**Exec Dt:** 10/23/2000

TSUTSUMI, KIYOHARU

**Exec Dt:** 10/23/2000

TAKARAGI, AKIRA

**Exec Dt:** 10/23/2000

INOUE, KEIZO

**Exec Dt:** 10/23/2000

**Assignee:** DAICEL CHEMICAL INDUSTRIES, LTD.

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**Correspondent:** BIRCH STEWART KOLASCH ET AL

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FALLS CHURCH, VIRGINIA 22040-0747

Search Results as of: 5/20/2003 6:34:27 P.M.

## Patent Assignment Abstract of Title

### Total Assignments: 1

Application #: 09463059

Filing Dt: 01/19/2000

Patent #: NONE

Issue Dt:

PCT #: NONE

Publication #: NONE

Pub Dt:

Inventor: TATSUYA NAKANO

Title: ACID-SENSITIVE COMPOUND AND RESIN COMPOSITION FOR PHOTORESIST

### Assignment: 1

Reel/Frame: 010634/0922

Received:  
03/29/2000

Recorded:  
01/19/2000

Mailed:  
06/05/2000

Pages: 3

Conveyance: ASSIGNMENT OF ASSIGNORS INTEREST (SEE DOCUMENT FOR DETAILS).

Assignor: NAKANO, TATSUYA

Exec Dt: 01/08/2000

Assignee: DAICEL CHEMICAL INDUSTRIES, LTD.

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OSAKA 590-8501, JAPAN

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Search Results as of: 5/20/2003 6:28:02 P.M.

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If you have any comments or questions concerning the data displayed, contact OPR / Assignments at 703-308-9723  
Web interface last modified: Oct. 5, 2002